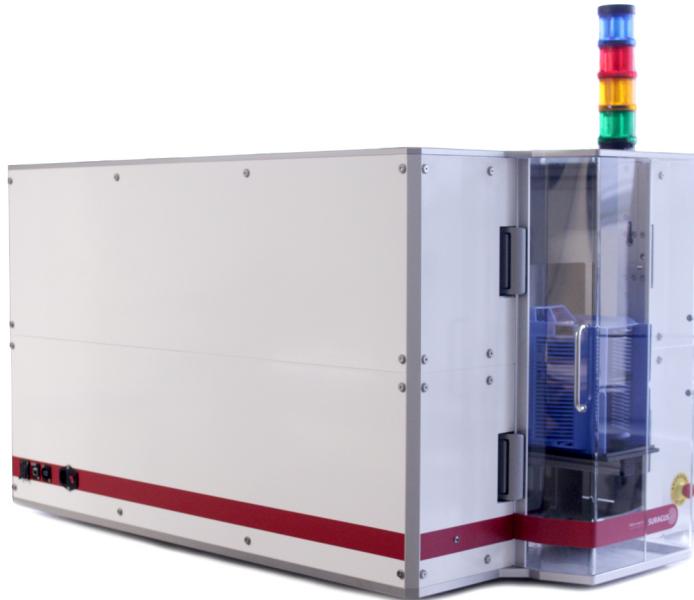


EddyCus® map C2C – Automated Resistivity Imaging Device

P_C2CRM_25



Highlights

- ▶ Contact-free
- ▶ Automated wafer handling
- ▶ Fast (one measurement within 60 seconds)
- ▶ High resolution (5 to 22,000) points
- ▶ Repeatable and accurate
- ▶ Customized setups
- ▶ Without edge grip

Parameters

- ▶ Resistivity (mOhm·cm)
- ▶ Sheet resistance (Ohm/sq)
- ▶ Metal layer thickness (nm, µm)
- ▶ Total thickness variation (µm)
- ▶ Defect and integrity assessment

SURAGUS GmbH
 Maria-Reiche-Strasse 1
 01109 Dresden
 Germany

For further questions:
 +49 351 32 111 520

sales@suragus.com

Visit us at:
www.suragus.com
www.suragus.com/calculator
www.suragus.com/EddyCusMapC2C

Applications

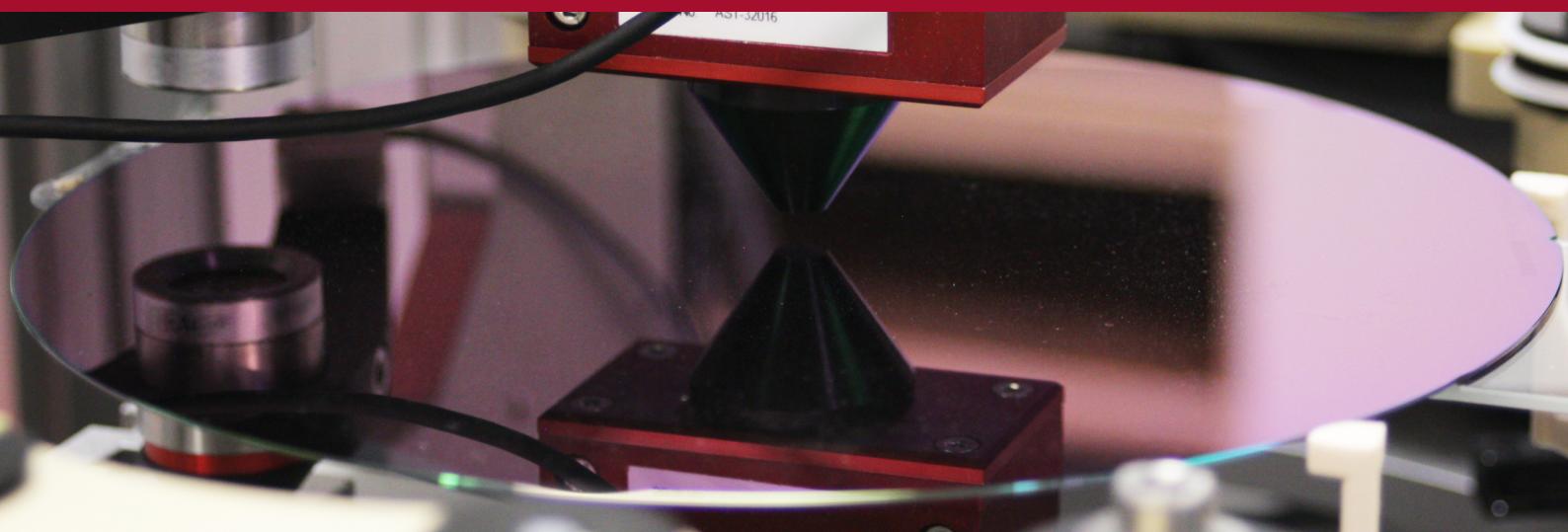
- ▶ Boule, puck and wafer characterization
- ▶ Layer deposition (PVD, CVD, plating ...)
- ▶ Epitaxy
- ▶ Implantation
- ▶ Doping
- ▶ Annealing
- ▶ Laser irradiation
- ▶ Etching
- ▶ Machining and Polishing
- ▶ Wafer sorting
- ▶ (De)-oxidation
- ▶ Defect imaging
- ▶ Final inspection

Materials

- ▶ Semiconductors
- ▶ Si
- ▶ SiC
- ▶ GaAs
- ▶ GaN
- ▶ Metal films
- ▶ Al
- ▶ Au
- ▶ Ti
- ▶ Cu
- ▶ Other conductive films and materials

Engineered and Made in Germany 





Measurement technology	Non-contact high frequency eddy current sensor, Confocal sensor for TTV
Substrates	6 / 8 inch wafer
Wafer thickness range	300 – 1,300 µm (other on request)
Cassettes	1
Edge effect correction / exclusion	2 – 10 mm (depending on size, range, setup and requirements)
Resistivity range	0.1 – 1,000 mOhm·cm < 1 – 3 % accuracy
Thickness measurement of metal films (e.g. Aluminum, Copper)	2 nm – 2 mm (in accordance with sheet resistance)
Measurement patterns	Standard ~ 22 000 points Points 9 / 17 / 49 / 81 / 99 / 169 / 625 / / 100,000
Measurement time	30 – 90 s per wafer depending on measurement points
Rotation speed	2 Hz
Throughput	45 wafers per hour (~ 22 000 measurement points per wafer)
Device dimensions (w/d/h)	785 mm x 1,170 mm x 666 mm / 30.91" x 46.06" x 26.22"
Available features	Sheet resistance, metal thickness, TTV, Carrier ID reader

Software and Handling

- ▶ Web Interface
- ▶ Easy to use software
- ▶ Recipe Management to adjust thresholds, data processing pipelines, result export options and more
- ▶ Display of mapping with intuitive graphical analysis tools
- ▶ Access Level for user profiles
- ▶ Extensive Job Management
 - ▶ Creation of default jobs for 150 and 200mm
 - ▶ Freely customizable sequence Jobs
 - ▶ Single Wafer analysis
- ▶ Result download via Webpage / API / FTP (future) / SECS-GEM (extrem future)
- ▶ Creation of statistics for mappings and thickness measurements

